



## ARCHIVE 2007

## PUSHING THE POWER/THERMAL ENVELOPE

## "Comparison of Methods for Measuring Residual Stresses in Connector Alloy Strip for BiTS Applications"

John Harkness, FASM Brush Wellman, Inc.

## "Socket and Heat Sink Considerations in High Power Burn-in"

John McElreath Micro Control Company

## "Determining Thermal Resistance Characteristics Without a Power Sensor"

Trent Johnson AMD Jerry Tustaniwskyj Delta Design

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## COMPARISON OF METHODS FOR MEASURING RESIDUAL STRESSES IN CONNECTOR ALLOY STRIP FOR BITS APPLICATIONS

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2007 Burn-in and Test Socket Workshop March 11 - 14, 2007

# OUTLINE

- Background of BiTS-grade strip
- Introduction to residual stresses in strip
- Questions
- Comparison of residual stress tests
  - X-Ray Diffraction
  - Wire-EDM Finger Test
  - Etch-to-1/2 Thickness Test
- Example results Cu-Be strip
- Cu-Be results vs. literature
- Conclusions
- Future work





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# BACKGROUND

## BiTS contact requirements

- Co-planar & dimensionally uniform STAMPED parts
- Low/uniform/predictable AGING distortion
  - Reason: consistent spring performance in large grid arrays
- One widely perceived cause of problem = variable distortion from high/non-uniform residual stresses in strip
- **Opportunity** ... provide the industry with "BiTSgrade", dimensionally stable strip via processing for low/uniform residual stress

## **Residual Stress (I) Definition & Origin in Cold Rolled Strip RESIDUAL STRESS** = The stress (Compressive or Tensile) which exists in an elastic solid body in the absence of, or in addition to, the stresses caused by an external load. Such stresses can arise in strip from NON-UNIFORM or localized deformation during rolling or stamping ... even brushing. Sheet Large Rolls

Local surface deformation: **COMPRESSIVE** surface & underlying TENSILE residual stress



Light Passes



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#### **Residual Stress (II) Basic "Tool Kit" for Management & Control** • References: text books, literature, patents • Deliberate "management" - Cold rolling practice - Surface treatment to impart desirable COMPRESSIVE stress (e.g., shot peening) Residual stress "reduction" SION LEVELER - Thermal stress relief ... Render YS < residual stress (enable distortion for **[STRETCH BEND** residual stress relief) LEVELER has - Mechanical stress relief (e.g., Tension more "robust" or Stretch Bend Leveling) ... PLASTICALLY DEFORM strip to **Roller Leveling** (BENDING)] override original stress distribution Combined "management" + "reduction"

Questions (I)
<ul> <li>What stress distribution in strip is "best" for BiTS?</li> <li>COMPRESSIVE surface stress enhances fatigue &amp; corrosion resistance in engineering applications</li> <li>TENSILE surface stress degrades Spring Bend Limit</li> <li>Is ZERO stress "good" or "bad" in connectors?</li> </ul>
<ul> <li>No references in literature</li> <li>How does stress vary over a large coil &amp; does that alter part distortion between slit cuts/down length?</li> <li>Does slitting "release" as-shipped stress?</li> </ul>
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> XRD Stress Tester

## X-Ray Diffraction (XRD) Test

- Determine X-Ray Elastic Constant (XEC)
  - Change in XRD peak vs. stress in 4-point bend test
  - Alloy 25 unaged < Brush 60 aged < Alloy 25 aged
- Cu-Be settings = {311} peak, Mn target, no filter
   10-12 exposures (10-13 minutes)/data point
- Data types
  - Surface residual stress
    - Line scan L, T or "contour map"
  - Through-thickness stress PROFILE
    - Surface to mid-plane -- serial etch
- Stress = DIRECTIONAL (L, T, 45 deg)
- Specimen size
  - Sheared sheets, slit cuts & stamped parts
- Typical cost (2006)
  - VENDOR = \$100/data point, \$40/etch step, \$1500/XEC test





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# **Conclusions (II)**

- "Baseline" stresses in today's Cu-Be strip
  - Surface COMPRESSIVE stresses in ALL Cu-Be (good)
  - <u>Through-t</u> stress profiles in **unaged** strip change to ZERO, then slightly TENSILE with depth
  - Tension Leveling → surface residual stress MORE COMPRESSIVE; mid-plane MORE TENSILE
    - T/L = LESS UNIFORM surface stress
  - Stretch Bend Leveling → apparently have not yet achieved EFFECTIVE mechanical stress relief
  - Aging of Alloy 25 (600 F/2 hr)
    - <u>Surface</u> stress = MORE COMPRESSIVE (NOT T/L), LESS COMPRESSIVE (T/L) ... ½ Hard
    - <u>Stress profile</u> approaches ZERO (NOT T/L) ... Hard
       <u>Aging imparts some "thermal stress relief"</u>



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## **Future Work**

- IMPLEMENT cost-effective residual stress test
  - Etch Test = Process development & inspection
  - **XRD** = R & D tool
- CONFIRM residual stress -- distortion correlation in stamped & aged BiTS parts
  - More "discriminating" BiTS customer trial(s)
- DEVELOP a proprietary process to make BiTS strip with a preferred residual stress distribution for dimension stability as-stamped & after age hardening
  - Guide development by residual stress testing

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# Socket and Heat Sink Considerations in High Power Burn-In



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## **Burn-In Example**

Desired Burn-In Temp =150 Degrees C No Individual Temperature Control Device Power Plus or Minus 40% Oven Airflow Plus or Minus 30% Low Temperature Device = 135.8 High Temperature Device = 167.2

Low Temperature Device Will Take 4.14 Times As Long to Burn-In

> Using Acceleration Factor as defined in A.T.& T. Reliability Manual: Klinger, Nakada, Menendez

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## Interface Factors Affecting Burn-In

- → 1. Interface Selection and Issues Rds
  - 2. Heat Flow Through BIB
  - 3. HeatSink Considerations
  - 4. Temperature Measurement
  - 5. Burn-In Chamber Layout Considerations
  - Conclusion

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## BIB Design Factors Affecting Burn-In

- 1. Interface Selection and Issues
- 2. Heat Flow Through BIB Rba
  - 3. HeatSink Considerations
  - 4. Temperature Measurement
  - 5. Burn-In Chamber Layout Considerations
  - Conclusion

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# Dipical BIB to Air Resistance balaxies for Various Pin Coult balaxies for Various Pin Coult balaxies 208 Pins ~ 11 °C/W 200 Pins ~ 6 °C/W 2000 Pins ~ 1.5 - 2 °C/W With Todut - Tair = 140°C on a 2000 pin balaxies for Approx. 80 Watts may go into BIB



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## Chamber Layout Factors Affecting Burn-In

- 1. Interface Selection and Issues
- 2. Heat Flow Through BIB
- 3. HeatSink Considerations
- 4. Temperature Measurement
- ► 5. Burn-In Chamber Layout Considerations
  - Conclusion

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## Burn-In Temperature Variation Versus Power and Air Flow Fluctuation

	-30% Air	Nominal Air	+30% Air
	Flow	Flow	Flow
+40% Power	159.3	152.9	148.9
Nominal Power	148.1	143.5 Deg. C	140.6
-40% Power	136.9	134.1	132.4





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## Chamber Specific Airflow Considerations Air Flow Versus DUT's per BIB Cha



Chamber Airflow Characteristics Needed Whether Air Flow is Controlled via a Socket Level Fan or Chamber Tray

## Conclusion

- Determining how to burn-in a Device during the design phases, may create an easier to test component.
- Fully understanding the chamber specific characteristics will yield the most effective burn-in solution. What does the Thermal Circuit look like?
- Developing tools for evaluating properties of materials, verifying designs, and calibrating measurement tools will get all the Devices to the bottom of the Bathtub.





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# Determining Thermal Resistance Characteristics Without a Power Sensor

2007 Burn-in and Test Socket Workshop March 12, 2007



Trent Johnson, AMD Jerry Tustaniwskyj, Delta Design





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## **Second Method** (experimental results) • Resulting curve fits the mathematical model: $T_{d}(t) \approx T_{d\infty} - C_{1}e^{-t/\tau_{1}} - C_{2}e^{-t/\tau_{2}}$ $\tau_1 \& \tau_2$ are time constants that are functions of thermal resistance $\theta_{h-l}$ (TIM2) Limitations on correlation to θ<sub>h-l</sub>: - Slow sample rate and/or inconsistent sample period $-\tau_1$ and $\tau_2$ are also a function of TIM1 and interactions with ambient conditions Note that high current applications require low electrical resistance $- \Rightarrow$ low thermal resistance to ambient Determining Thermal Resistance Characteristics March 12, 2007 Without a Power Sensor



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# Second Method (wide deployment results)

• Histogram shows a normal distribution with a tail of abnormal results









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	Method 1	Method 2	Method 3
Works	×		$\checkmark$
Currently in use	×		×
Most accurate	×	?	?
Fastest	×	×	
Can work on all systems @ AMD	×		×



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